

Form PTO-1449 (REV. 8-83)			US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 125640		APPLICATION NO. 10/553,675	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)								
			APPLICANTS Satoshi TAKEI et al.					
			FILING DATE October 31, 2005					
U.S. PATENT DOCUMENTS								
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME		CLASS	SUB CLASS	
	1	5,919,599	07/06/1999	Meador et al.				
	2	5,693,691	12/02/1997	Flaim et al.				
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY		CLASS	SUB CLASS	
/DD/	3	JP A 2000-294504 w/abstr. + trans.	10/20/2000	Japan				
/DD/	4	JP A 2002-47430 w/abstr. + trans.	02/12/2002	Japan				
/DD/	5	JP A 2002-190519 w/abstr. + trans.	07/05/2002	Japan				
/DD/	6	JP A 2002-128847 w/abstr. + trans.	05/09/2002	Japan				
/DD/	7	JP A 2002-207295 w/abstr. + trans.	07/26/2002	Japan				
/DD/	8	JP A 2002-207296 w/abstr. + trans.	07/26/2002	Japan				
/DD/	9	JP A 2003-57828 w/abstr. + trans.	02/28/2003	Japan				
/DD/	10	JP A 2001-272506 w/abstr. + trans.	10/05/2001	Japan				
/DD/	11	JP A 2000-512402 w/translation	09/19/2000	Japan				
	12	WO 02/05035 A1 w/abstract	01/17/2002	WIPO				
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)								
/DD/	13	Lynch et al., "Properties and Performance of Near UV Reflectivity Control Layers," SPIE Vol. 2195, pp. 225-229, 1994						
/DD/	14	Taylor et al., "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography," SPIE Vol. 3678, pp. 174-185, March 1999						
/DD/	15	Meador et al., "Recent Progress in 193 nm Antireflective Coatings," SPIE Vol. 3678, pp. 800-809, March 1999						
EXAMINER /Duy Vu Deo/ (04/25/2007)						DATE CONSIDERED		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

Date: December 19, 2005